China Best factory price Cylinder Gas wholesale high purity sih4 Silane N2 Gas Mixture

Our Product Introduction

Basic Information

- Place of Origin: China
- Brand Name: CMC
- Certification: COA
- Model Number: sih4
- Minimum Order Quantity: 1kg
- Price: US $45/kg
- Packaging Details: Cylinder/Tank
- Delivery Time: 15 days
- Payment Terms: L/C, T/T
- Supply Ability: 5000kg/month

Product Specification

- Product Name: Sih4
- Purity: 99.99%
- FormulaTsih4/N2 ConstituentTindustria: 12.5MPa/15MPa/20MPa
- Chemical: Non-Flammable Gas
- Transport Package: 40L/47L/50L
- Specification: 40L/47L/50L
- Trademark: CMC
- Origin: China
- HS Code: 280430000
- Supply Ability: 500, 000m3/Year
- CAS No.: Sih4/N2
- Formula: Sih4/N2
- Constituent: Industrial Pure Air
- Grade Standard: Electronic Grade, Industrial Grade

More Images

Product Description

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Silane and nitrogen (N2) mixed gas refers to a combination of the silane gas (SiH4) and nitrogen gas. This mixture can be created by blending the two gases in specific ratios. Here are a few points regarding silane nitrogen mixed gas:

Purpose: The use of silane nitrogen mixed gas can serve various purposes depending on the specific application. The addition of nitrogen to silane gas can alter its properties and allow for controlled processes.

Dilution: Nitrogen is often added to silane gas to dilute its concentration. Diluting silane with nitrogen can be done to reduce its reactivity and lower the risk of unwanted reactions or hazards.

Safety: Silane is a flammable and highly reactive gas, and mixing it with nitrogen can provide a safer working environment. The addition of inert nitrogen gas can help to stabilize the mixture and reduce the risk of combustion or explosions.

Applications: Silane nitrogen mixed gas finds applications in various industries, including:

Semiconductor Industry: Silane nitrogen mixtures can be used in chemical vapor deposition (CVD) processes for the deposition of silicon-based films in semiconductor manufacturing. The addition of nitrogen can modify the film properties, such as refractive index or stress.

Solar Cell Production: Silane nitrogen mixtures can be employed in the manufacturing of silicon-based solar cells. It is used as a precursor gas for the deposition of thin films on solar cell substrates.

Coating and Surface Modification: Silane nitrogen mixtures can be utilized as precursor gases in surface treatment processes, such as plasma-enhanced chemical vapor deposition (PECVD) or atomic layer deposition (ALD). These processes can be employed for coating or modifying the surface properties of various materials.

It is important to note that the specific composition and application of silane nitrogen mixed gas may vary depending on the desired outcome and safety considerations. Proper handling, storage, and usage precautions should be followed when working with any gas mixture.

Specification:

COMPOSITION / INFORMATION ON INGREDIENTS			
CAS	Component Name	Purity	Percent
7727-37-9	Nitrogen	99.9999%	80%
7803-62-5	Silane	99.9999%	20%
UN No.	1954		
DOT Class	2.1		
Label	Flammable Gas		

Packaging & Shipping

Cylinder Specifications		Contents	Pressure	
Cylinder Capacity	Valve	Volume	bar	psig
40L	CGA350	3200L	80	1160

Company Profile

ShangHai CMC chemical Co.,ltd. is staffed by trained personnel, combine many years experience in Gas industry .We supply cylinder gas, electronic gas, etc ., and the gas holder, panel, valves and fittings and other equipment, parts and engineering services to our customers in China and worldwide; The products are involved in various industrial fields, such as semiconductor chip, solar cell, LED, TFT-LCD, optical fiber, glass, laser, medicine , etc., Our mission is to partner with our global customers to provide support, solutions and quality products that are innovative,reliable, and safe.
Our products mainly include: H2, O2, N2, Ar, CO2, propane, acetylene, helium, laser mixed gas, SiH4, Sih2cl2, SiHCL3, SiCL4, NH3, CF4, NF3, SF6, HCL, N2O, doping mixed gas (TMB, PH3, B2H6) and other electronic gases.

SiCl4	NH3	NH3	CH3F	SiH4	Kr	H2S	WF6	F6+Cl2
4MS	C3F8	C3F8	TEOS	CH4	PH3	SF6	C2	HCl+Ne
CF4	C4F8	SiH2						TMB+H2
SiF4	C3H8	Cl2						He +As
BBr3	C3H6	DCE						Ge+Se
POCl3	N2	SO2						D+B
BCl3	D2	CO2						CO+NO
SiHCl3	CH2F2	HF	AsH3	C2H4	C2H2	HBr	COS	Ar+O2
TMAl	DMZn	DEZn	GeH4	C2H6	B2H6	H2Se	GeCl4	Xe+NO

Workshop Display:

Monitor

Laboratory

Equipment

Zone of rectification

Gas filling

Equipment